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TECHNOLOGY CENTER 2800

**In re Application of:**

Pan et al.

**Serial No.:** 09/073,494

**Filed:** May 6, 1998

**For:** TECHNIQUE FOR ELIMINATION OF  
PITTING ON SILICON SUBSTRATE  
DURING GATE STACK ETCH

**Examiner:** H. Vu

**Group Art Unit:** 2811

**Attorney Docket No.:** 2915.1US (96-149.1)

Express Mail Mailing Label No.: EL 740549789 US 8-31-01

Date of Deposit with USPS: August 24, 2001

Person making Deposit: Jared Turner

21/F  
FJONES

**PRELIMINARY AMENDMENT**

**Box RCE**

Hon. Assistant Commissioner for Patents  
Washington, D.C. 20231

Sir:

Prior to examination of the claims on the merits in the above-identified application,  
please amend this application as follows:

**IN THE CLAIMS:**

Please note that all claims currently pending and under consideration in the referenced  
application are shown below, in clean form, for clarity. A marked up version of the claims with  
amendments is attached hereto.

TRASKBRITT, PC  
ATTY. REF. NO. 2915.1US(96-149.1)